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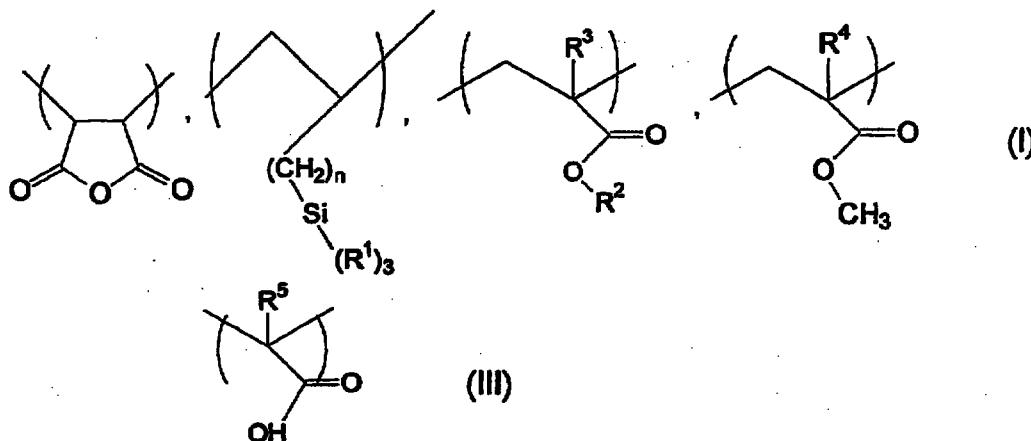
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(54) Title: RADIATION SENSITIVE COPOLYMERS, PHOTORESIST COMPOSITIONS THEREOF AND DEEP UV BILAYER SYSTEMS THEREOF



(57) Abstract: Radiation sensitive resins for use in a top layer resists in bilayer systems for use in deep UV photolithography comprises copolymers having structural units (I) and optionally (III), wherein n is an integer of 1 to 5,  $R^1$  is methyl or trimethylsiloxy,  $R^2$  is a tert-butyl group,  $R^3$ ,  $R^4$  and  $R^5$  are each independently hydrogen or a methyl group.